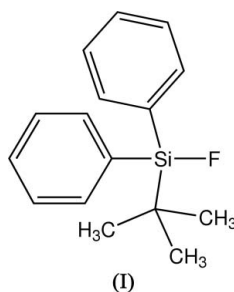


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Key indicators

Single-crystal X-ray study
 $T = 173$ K
Mean $\sigma(\text{C}-\text{C}) = 0.003$ Å
 R factor = 0.038
 wR factor = 0.095
Data-to-parameter ratio = 20.3For details of how these key indicators were
automatically derived from the article, see
<http://journals.iucr.org/e>.*tert*-ButylfluorodiphenylsilaneIn the title compound, $\text{C}_{16}\text{H}_{19}\text{FSi}$, the Si atom approximates the expected tetrahedral geometry, with an Si–F bond length of 1.6004 (10) Å.Received 3 March 2006
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Comment

In the title compound, (I), the Si atom shows a slightly distorted tetrahedral configuration, with bond angles ranging from 105.43 (6) (F1–Si1–C21) to 113.69 (7)° (C1–Si1–C21). The Si1–F1 bond length of 1.6004 (10) Å is as expected and is comparable with that in fluorotri-*o*-tolylsilane [Si–F = 1.601 (1) Å at 298 K; Dell *et al.*, 1999].

Experimental

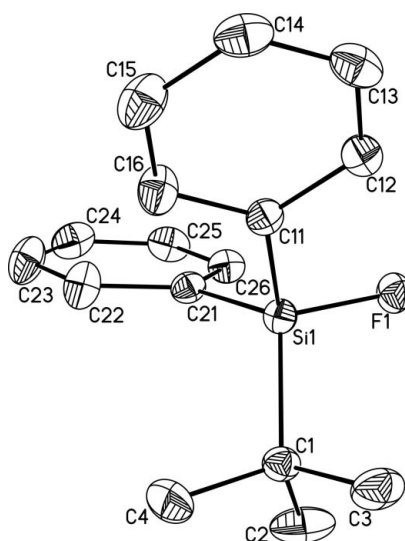
The synthesis of (I) will be described elsewhere (Schirmacher *et al.*, 2006). In contrast to earlier findings (Damrauer *et al.*, 1988), compound (I) crystallized spontaneously from the melt after it had been distilled *in vacuo*.

Figure 1
View of (I), showing the labelling scheme and displacement ellipsoids drawn at the 30% probability level. H atoms have been omitted.

Crystal data

C₁₆H₁₉FSi
M_r = 258.40
 Monoclinic, *P*2₁/*c*
a = 9.5029 (8) Å
b = 22.984 (2) Å
c = 7.2776 (5) Å
 β = 112.226 (5)°
V = 1471.4 (2) Å³
Z = 4

D_x = 1.166 Mg m⁻³
 Mo *K*α radiation
 Cell parameters from 14895 reflections
 θ = 2.9–27.5°
 μ = 0.15 mm⁻¹
T = 173 (1) K
 Block, colourless
 0.26 × 0.24 × 0.24 mm

Data collection

Nonius KappaCCD diffractometer
 ω scans
 Absorption correction: none
 14895 measured reflections
 3366 independent reflections
 1836 reflections with *I* > 2σ(*I*)

*R*_{int} = 0.048
 θ_{\max} = 27.5°
h = -12 → 11
k = -29 → 29
l = -9 → 9

Refinement

Refinement on *F*²
R [*F*² > 2σ(*F*²)] = 0.038
wR (*F*²) = 0.095
S = 0.80
 3366 reflections
 166 parameters

H-atom parameters constrained
 $w = 1/[\sigma^2(F_o^2) + (0.0518P)^2]$
 where $P = (F_o^2 + 2F_c^2)/3$
 (Δ/σ)_{max} < 0.001
 $\Delta\rho_{\max} = 0.26 \text{ e } \text{Å}^{-3}$
 $\Delta\rho_{\min} = -0.18 \text{ e } \text{Å}^{-3}$

All H atoms were placed in calculated positions and refined using a riding model, with *U*_{iso}(H) = 1.5*U*_{eq}(C) for methyl groups and *U*_{iso} =

1.2*U*_{eq}(C) for aryl groups. The methyl groups were allowed to rotate but not to tip. Constrained CH bond lengths: 0.93 Å for aryl CH and 0.96 Å for methyl CH₃.

Data collection: *COLLECT* (Nonius, 1998); cell refinement: *DENZO* and *SCALEPACK* (Otwinowski & Minor, 1997); data reduction: *DENZO* and *SCALEPACK*; program(s) used to solve structure: *SHELXS97* (Sheldrick, 1997); program(s) used to refine structure: *SHELXL97* (Sheldrick, 1997); molecular graphics: *SHELXTL-Plus* (Sheldrick, 1991); software used to prepare material for publication: *SHELXL97* and *PLATON* (Spek, 2003).

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